

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 08-339895

(43)Date of publication of application : 24.12.1996

(51)Int.Cl.

H05H 1/46  
C23F 4/00  
H01L 21/203  
H01L 21/205  
H01L 21/3065

(21)Application number : 07-169209

(71)Applicant : TOKYO ELECTRON LTD  
TOKYO ELECTRON YAMANASHI KK

(22)Date of filing : 12.06.1995

(72)Inventor : AOKI MAKOTO

## (54) PLASMA PROCESSING DEVICE

### (57)Abstract:

**PURPOSE:** To improve a useful period of a quartz member also to perform a stable plasma process, by confining plasma, generated in a processing vessel, in a prescribed part, and protecting a quartz member, provided in the processing vessel, from corrosion by the plasma for generating the plasma of high density.

**CONSTITUTION:** A quartz-made annular shield ring 25 is fitted to a peripheral part of an upper part electrode 2, to provide a quartz-made annular focus ring 19 in a peripheral part of a wafer W on a lower part electrode 3. Alumina system ceramic layers 20, 26, which are a member having corrosion resistance higher than quartz relating to plasma, are provided in a surface relating to the plasma of these quartz-made rings.

